

Origin of enhanced thermal atomic layer etching of amorphous HfO₂

URL: <https://avs.scitation.org/doi/10.1116/6.0001614>

Authors: [Mullins, Rita](#) / [Gutiérrez-Moreno, Julio](#) / [Nolan, Michael](#)

Research Lines: [Ab-Initio Electronic Structure Methods](#)

Publication: Journal of Vacuum Science & Technology

Place Published: AVS

Volume / Pagination: 40 / 022604

Paraules clau: [amorphous](#), [Atomic Layer Etching](#), [HfO₂](#), [surfaces](#)

Barcelona Supercomputing Center - Centro Nacional de Supercomputación

Source URL (retrieved on 19 nov 2024 - 15:31): <https://www.bsc.es/ca/research-and-development/publications/origin-enhanced-thermal-atomic-layer-etching-amorphous-hfo2>